

**Properties of iridium-inserted nickel silicides by thermal annealing of the Ni/Ir bilayer on silicon and polysilicon substrates**

Song O, Yoon K.

Metals and materials international

2007; 13(3):229-234

**ARTICLE IDENTIFIERS**

DOI: 10.1007/BF03027810

PMID: unavailable

PMCID: not available

**JOURNAL IDENTIFIERS**

LCCN: not available

pISSN: 1225-9438

eISSN: 1598-9623

OCLC ID: not available

CONS ID: not available

US National Library of Medicine ID: not available

This article was identified from a query of the SafetyLit database.